L Number	Hits	Search Text	DB	Time stamp
1	1	6066030.pn.	USPAT	2003/12/01 10:08
--	27241	(cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)	USPAT	2003/12/01 10:08
--	1068	((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)	USPAT	2003/11/05 14:27
--	255	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)	USPAT	2003/11/05 13:16
--	251	((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)) and @ay<=2001	USPAT	2003/11/05 13:17
--	228	((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)) and @ay<=2000	USPAT	2003/11/05 15:11
--	17	(((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)) and @ay<=2000) and (cmp or polish or polished or polishing or planarizing or planarize).ab.	USPAT	2003/11/05 13:38
--	159	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.	USPAT	2003/11/05 13:38
--	128	((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.) and @aY<=2000	USPAT	2003/11/05 13:38
--	950	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and @ay<=2000	USPAT	2003/11/05 14:27
--	108	((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and @ay<=2000) and shear	USPAT	2003/11/05 14:27
--	87	(((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and @ay<=2000) and shear) not (((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.) and @aY<=2000)	USPAT	2003/11/05 14:28

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—	211	(((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)) and @ay<=2000) not ((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.)	USPAT	2003/11/05 15:11
—	198	((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cathode or anode or electrolytic or electrolyze)) and @ay<=2000) not ((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.)) not ((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and @ay<=2000) and shear) not (((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (chelate or chelating)) and (cmp or polish or polished or polishing or planarizing or planarize).ab.) and @aY<=2000))	USPAT	2003/11/05 15:11
—	9767	((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and parallel	USPAT	2003/11/05 15:45
—	889	((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and ((flow or flowing or jet or solution or slurry) with parallel)	USPAT	2003/11/05 15:46
—	54	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and ((flow or flowing or jet or solution or slurry) with parallel)) and (chelate or chelating or ligand)	USPAT	2003/11/05 15:46
—	27241	(cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)	USPAT	2003/11/06 10:33
—	8211	((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)	USPAT	2003/11/06 09:31
—	1247	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry	USPAT	2003/11/06 09:32
—	1322	(((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and (slurry or (polish$3 near3 solution))	USPAT	2003/11/06 09:32
—	1247	((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))	USPAT	2003/11/06 09:33
—	7514	(cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper)	USPAT	2003/11/06 09:34

-	684	(((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))) and ((cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper))	USPAT	2003/11/06 09:35
-	571	((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))) and ((cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper))) and @ay<=2000	USPAT	2003/11/06 09:35
-	150	(((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))) and ((cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper))) and @ay<=2000) and (chelate or chelating or additive or ligand)	USPAT	2003/11/06 09:36
-	884	(cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)	USPAT	2003/11/06 10:43
-	316	((cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)) and (copper or Cu)	USPAT	2003/11/06 10:33
-	299	(((cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)) and (copper or Cu)) and @ay<=2000	USPAT	2003/11/06 10:33
-	298	((((cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)) and (copper or Cu)) and @ay<=2000) not (((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))) and ((cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper))) and @ay<=2000) and (chelate or chelating or additive or ligand))	USPAT	2003/11/06 10:34
-	121	(cmp or polish or polished or polishing or planarizing or planarize) same (shear adj stress)	USPAT	2003/11/06 10:35
-	114	((cmp or polish or polished or polishing or planarizing or planarize) same (shear adj stress)) and @ay<=2000	USPAT	2003/11/06 10:36
-	114	(((cmp or polish or polished or polishing or planarizing or planarize) same (shear adj stress)) and @ay<=2000) not (((((((cmp or polish or polished or polishing or planarizing or planarize) and (cu or copper)) and (groove or (contact adj hole) or inter$1connection)) and slurry) and (slurry or (polish$3 near3 solution))) and ((cmp or polish or polished or polishing or planarizing or planarize) same (cu or copper))) and @ay<=2000) and (chelate or chelating or additive or ligand))	USPAT	2003/11/06 10:36

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–	251	(cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)	US-PGPUB; EPO; JPO; DERWENT	2003/11/06 10:43
–	42	((cmp or polish or polished or polishing or planarizing or planarize) and (shear adj stress)) and @ay<=2000	US-PGPUB; EPO; JPO; DERWENT	2003/11/06 10:44
–	7686	(cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)	USPAT	2003/11/26 16:37
–	991	((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode	USPAT	2003/11/26 16:38
–	688	(((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode	USPAT	2003/11/26 16:38
–	304	((((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode) and (electrolytic or electrolyze)	USPAT	2003/11/26 16:39
–	275	(((((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode) and (electrolytic or electrolyze)) and @ay<=2000	USPAT	2003/11/26 16:39
–	221	((((((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode) and (electrolytic or electrolyze)) and @ay<=2000) and ((voltage or power or current) with (cathode or anode))	USPAT	2003/11/26 16:47
–	60	(((((((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode) and (electrolytic or electrolyze)) and @ay<=2000) and ((voltage or power or current) with (cathode or anode))) and (electro$1polish or electro$1polishing)	USPAT	2003/11/26 16:51
–	529	(electro$1polish or electro$1polishing) and copper	USPAT	2003/11/26 16:51
–	566	(electro$1polish or electro$1polishing) and (copper or Cu)	USPAT	2003/11/26 16:51
–	273	((electro$1polish or electro$1polishing) and (copper or Cu)) and cathode	USPAT	2003/11/26 16:51
–	252	(((electro$1polish or electro$1polishing) and (copper or Cu)) and cathode) and @ay<=2000	USPAT	2003/11/26 16:51
–	192	((((electro$1polish or electro$1polishing) and (copper or Cu)) and cathode) and @ay<=2000) not ((((((((cmp or polish or polished or polishing or planarizing or planarize or electro$1polish or electro$1polishing) same (cu or copper)) and cathode) and anode) and (electrolytic or electrolyze)) and @ay<=2000) and ((voltage or power or current) with (cathode or anode))) and (electro$1polish or electro$1polishing))	USPAT	2003/11/26 16:52

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